HEMTO-TDS

Hydrogen-Sensitive Thermal Desorption Spectroscopy System



HEMTO-TDS is a thermal desorption spectroscopy (TDS) system designed to detect trace amounts of hydrogen from small-volume samples such as thin films. The highly hydrogen-sensitive detection is achieved by combining the efficient sample heating by infrared laser with the extremely low hydrogen background level maintained by a BeCu chamber. Equipped with a quadrupole mass spectrometer (QMS), the HEMTO-TDS is the ideal instrument for analyzing hydrogen with other desorbed gases.

- Extremely high sensitivity to hydrogen
- Non-contact temperature control by laser heating
- Productization of the Hosono laboratory TDS system (Tokyo Institute of Technology)

Specifications

	Detection limit $\sim 1 \times 10^{-13}$ A
Hydrogen ion current	Can detect H_2^+ from H^+ -implanted Si at 1×10^{15} ion/cm ²
	Can detect H_2^+ from samples containing 5×10^{16} /cm ³ (1 ppm) H-impurities
Heating method	Non-contact heating by infrared laser (983 nm)
	PID control by pyrometer (sample-emissivity calibration required)
Temperature control	Temperature range: 150 ~1000 °C
	Heating rate: arbitrary rate between 10-100 °C /min
Sample size	10mm×10mm
Mass analysis range	1-100 amu

Applications

- Hydrogen-impurity detection in semiconductor substrates
- Hydrogen-impurity detection in thin films
- TDS detection of impurities in small-volume samples
- Investigation of absorption/adsorption bonding states

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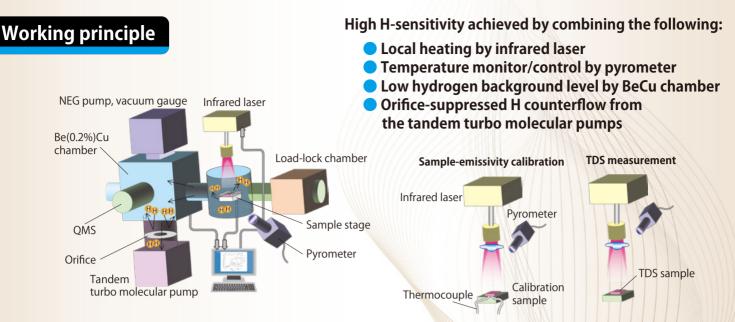
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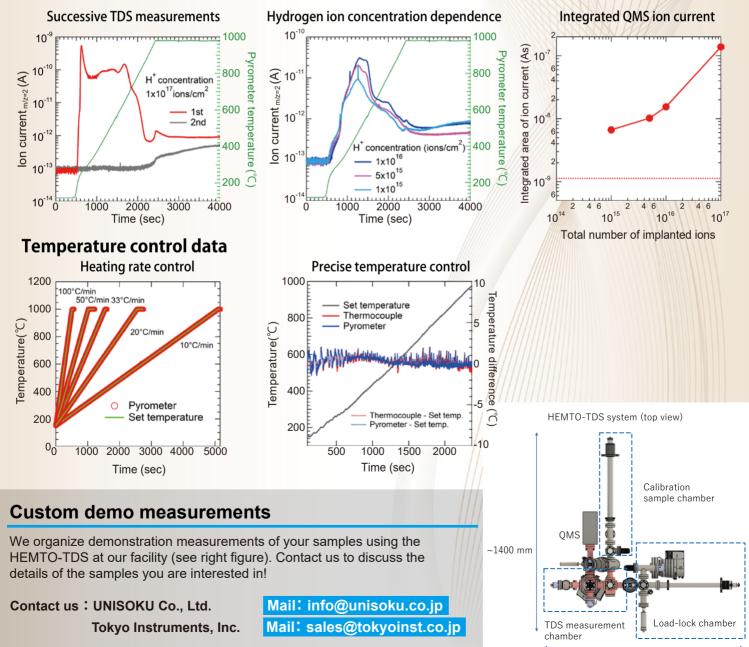
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The calibration and the TDS samples should be identical in terms of size, doping level, and surface conditions.

Example TDS data

TDS measurements of a H+-implanted Si substrate



~1300 mm